

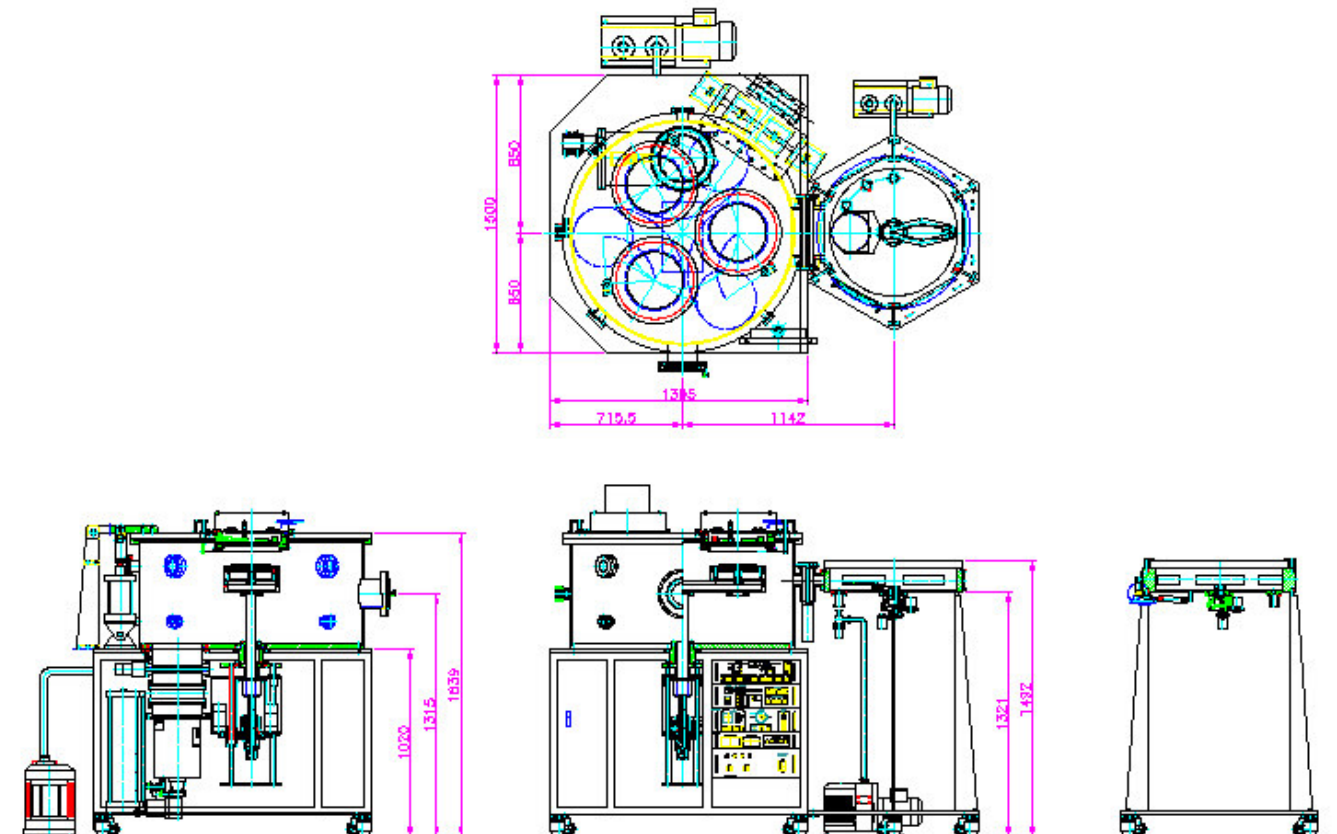
# ATS-PVD Series Magnetron Sputter System with 3x12" Guns



## Special Features

- ◆ Magnetron sputter system for R&D and small scale production
- ◆ High speed pumping system equipped with cryogenic pump
- ◆ Automatic robot loading system
- ◆ Automatic positioning system between guns and substrate
- ◆ Convenient control on touch screen
- ◆ Wafer capacity  
1 × 8"
- ◆ Average throughput  
Up to 5,000 wafers per year
- ◆ Dimension  
2,000L X 1,720H X 1,200W (mm)
- ◆ Others  
Power : AC 2kW (13.56MHz)  
DC 3kW  
Gas : Ar / O<sub>2</sub>  
Pump : rotary  
(970l/min for process chamber,  
600l/min for loadlock chamber)  
& cryo(25,000l/s)

◇ Layout



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